

ABSTRACT OF THE DISCLOSURE

To provide a method for manufacturing an electro-optical substrate having high reliability with high yield. The method for manufacturing an electro-optical substrate including a composite base plate obtained by joining a support plate to a semiconductor plate having single-crystal silicon precursor layer (semiconductor precursor layer) can include a step of forming a light-shielding layer, having a predetermined pattern, on the support plate, a step of forming an insulating layer on the light-shielding layer having the predetermined pattern, a step of providing semiconductor layers on the insulating layer, a step of oxidizing parts of the semiconductor layers to form oxide layers, and a step of removing the oxide layers. The oxide layers can have a thickness smaller than that of the insulating layer.